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PATENT  
2185-0590P

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IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Yasunori UETANI et al. Conf.: 8026  
Appl. No.: 09/988,006 Group: 1752  
Filed: November 16, 2001 Examiner: R. Ashton  
For: CHEMICALLY AMPLIFYING TYPE POSITIVE  
RESIST COMPOSITION

REPLY UNDER 37 C.F.R. § 1.111

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

June 10, 2003

Sir:

In reply to the Examiner's Office Action dated December 10, 2002, the due date having been extended three months, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

IN THE SPECIFICATION:

Please replace the paragraph beginning on page 1, line 9, with the following rewritten paragraph:

a  
--A lithography process using a resist composition has usually been adopted in the minute processing of a semiconductor. In lithography, the resolution can be improved with a decrease in wavelength of exposure light in principle as expressed by the equation of Rayleigh's diffraction limit. A g-line with a